



Application No.: 09/629,022  
Filed: July 31, 2000  
Group Art Unit: 2881

In the specification:

At page 1, line 1, delete in the title "Method and Apparatus for Measuring Features of a Semiconductor Device" and insert therefore, -- Apparatus for Measuring Features of a Semiconductor Device --.

In the claims:

1. (Amended) An apparatus for determining a dimension of a feature of a semiconductor device, comprising:

at least one source of electrons;

a focusing device positioned proximate to the source of electrons to focus electrons emitted by the source and form an electron beam, the focusing device focusing the electron beam to have a first depth and a second depth of focus and form at least one representation of the semiconductor device corresponding to electrons focused at the first and second depths of focus and impinging on the semiconductor device;

a support aligned with the electron beam and having a support surface to engage the semiconductor device and support the semiconductor device, one of the electron beam and the support being movable relative to the other of the electron beam and the support in any of the x, y, or z planes.

12. (Amended) An apparatus for determining a dimension of a feature of a semiconductor device, comprising:

a source of electrons;

*B3*  
*Ward*  
a port surface having a first and second ports therethrough, the first port being positioned proximate to the source to form a first electron beam when electrons pass therethrough, the second port spaced apart from the first port to form a second electron beam when electrons pass therethrough;

*B2*  
a first focusing device positioned proximate to the first port and adjacent the first electron beam to focus the first electron beam on a first position;

*B2*  
a second focusing device positioned proximate to the second port and adjacent the second electron beam to focus the second electron beam on a second position that is different from the first position; and

*B2*  
a support aligned with the first and second ports and having a support surface to engage the semiconductor device and support the semiconductor device at the first and second positions, one of the support and the source being movable relative to the other of the support and the source in any of the x, y, or z planes.

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20. (Amended) An apparatus for determining a dimension of a semiconductor device feature, comprising:

*B3*  
*Ward*  
first and second sources of electrons;

a first focusing device positioned proximate to the first source of electrons to focus a first electron beam emitted from the first source;

a second focusing device positioned proximate to the second source of electrons to focus a second electron beam emitted from the second source; and

a support aligned with the first and second focusing devices and configured to engage the semiconductor device, one of the support and the sources of electrons being movable relative to the other of the support and the sources of electrons in any of the x, y, or z planes.